

Ferromagnetic Semiconductors - Physics and Material Science -

H. Ohno

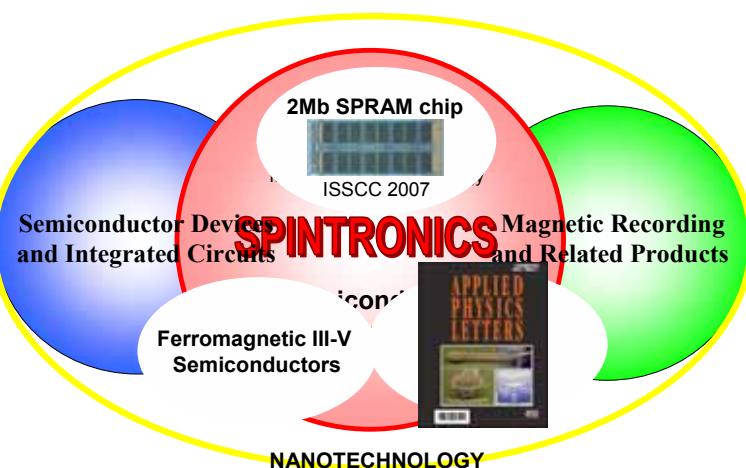
M. Yamanouchi, D. Chiba, T. Dietl, and F. Matsukura



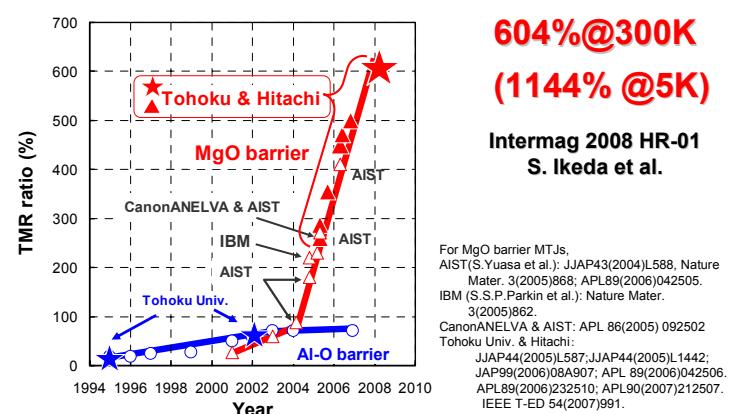
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program from the Ministry of Education, Culture, Sports, Science and Technology of Japan.

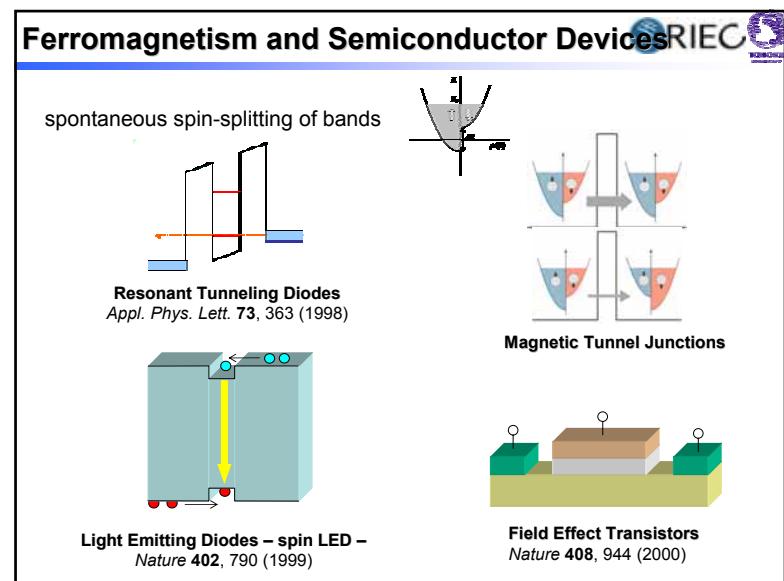
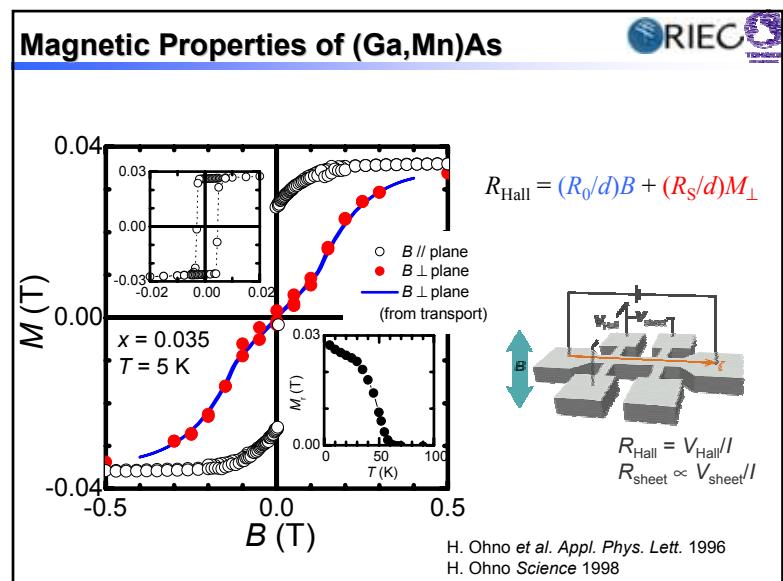
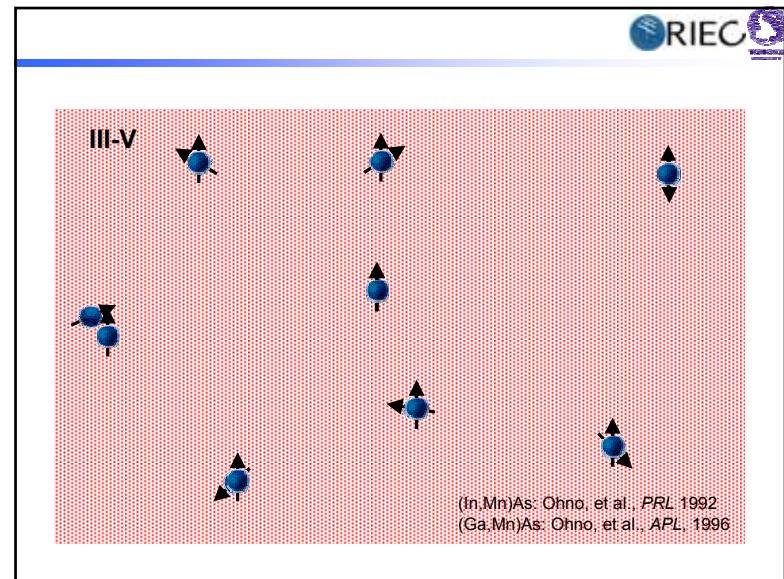
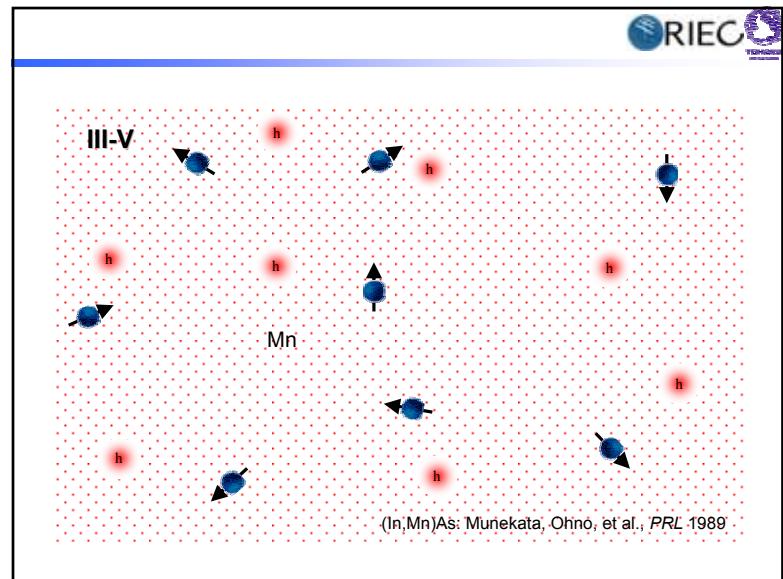
Why spintronics is important

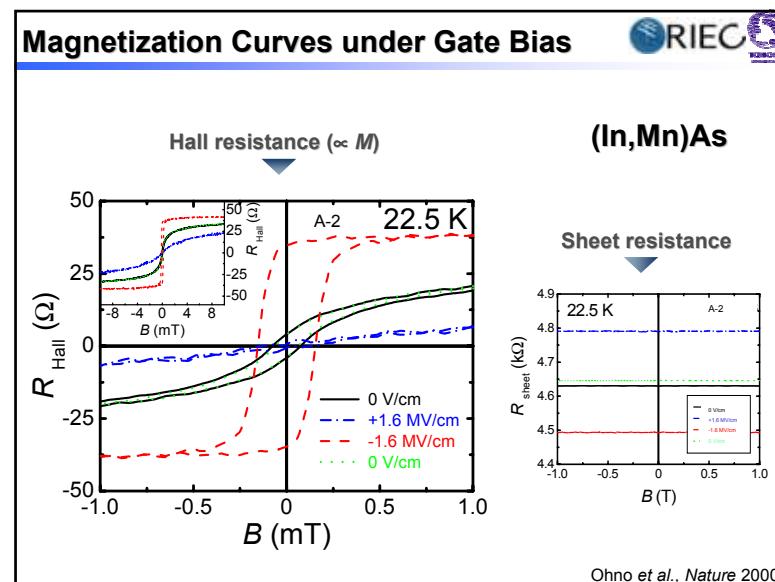
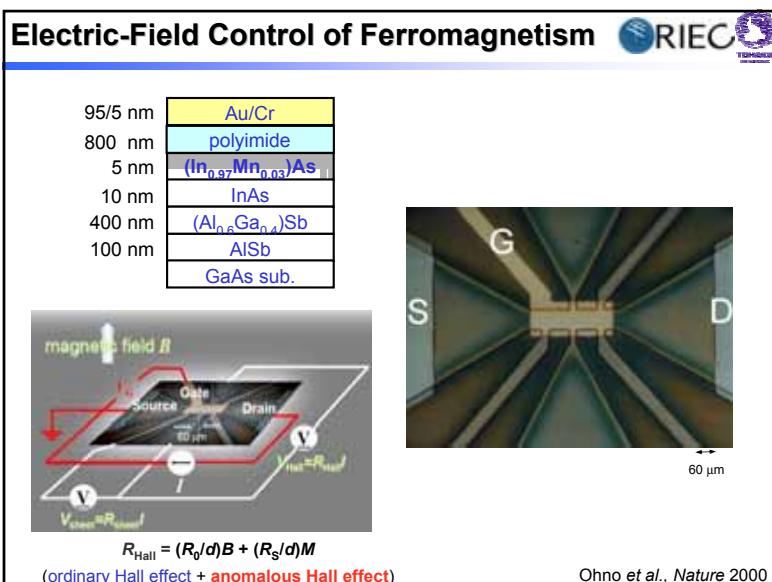
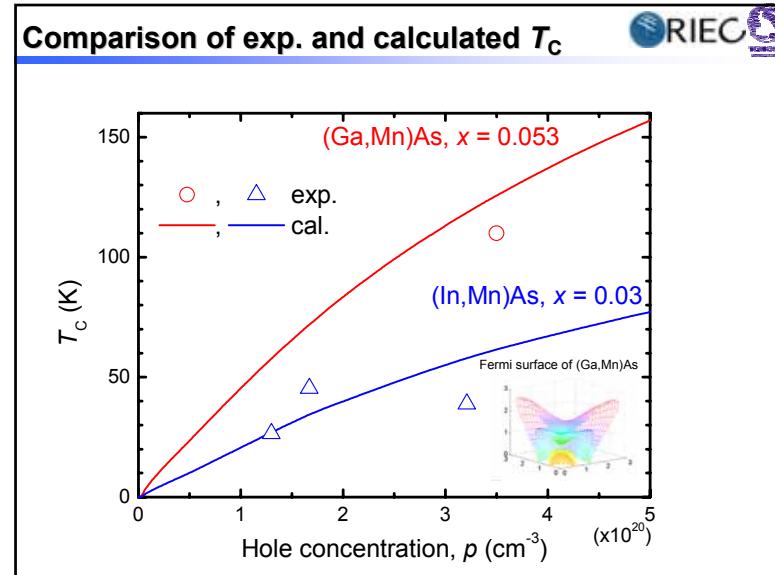
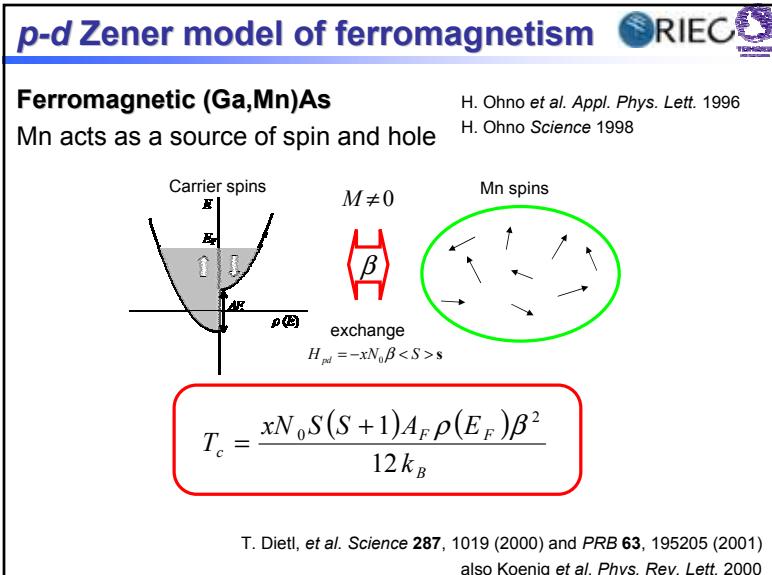


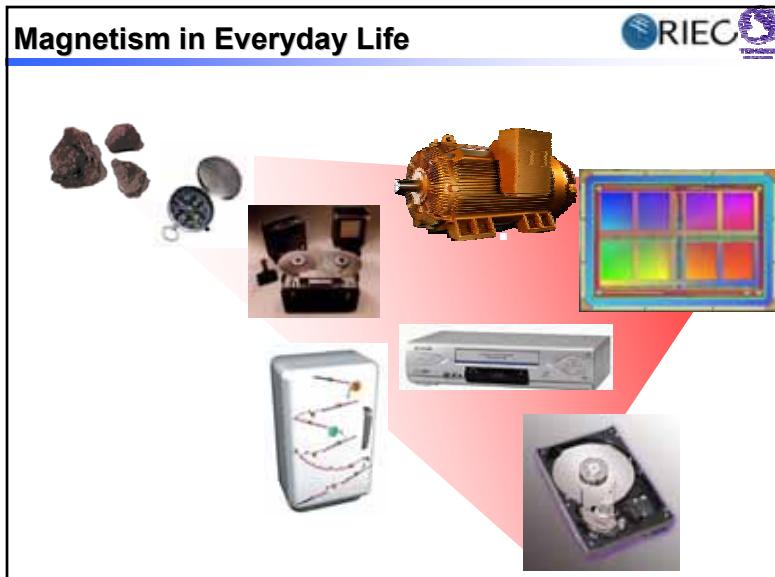
TMR ratio of MgO-MTJs



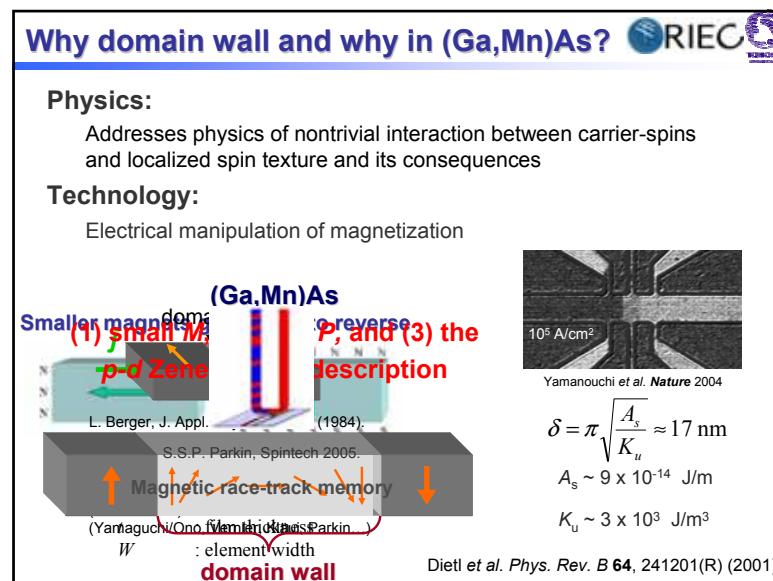
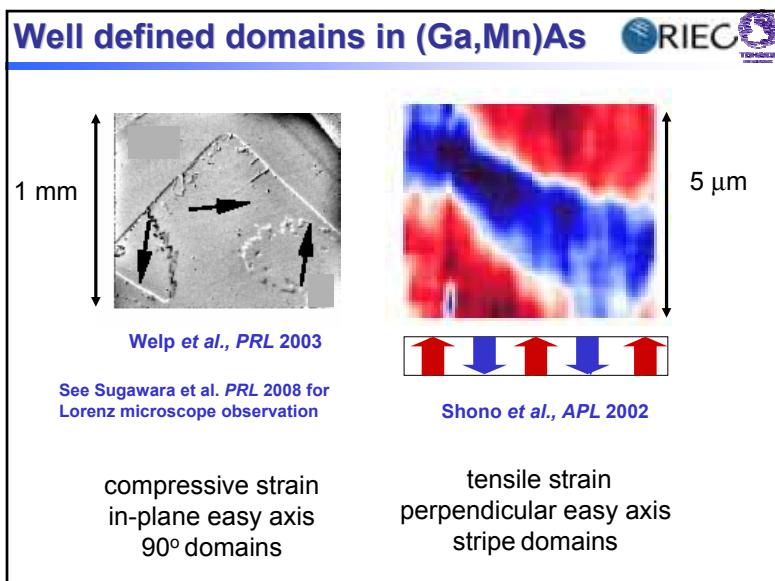
1. Ferromagnetic III-V semiconductors
2. Current-induced domain wall motion
3. Toward high T_c

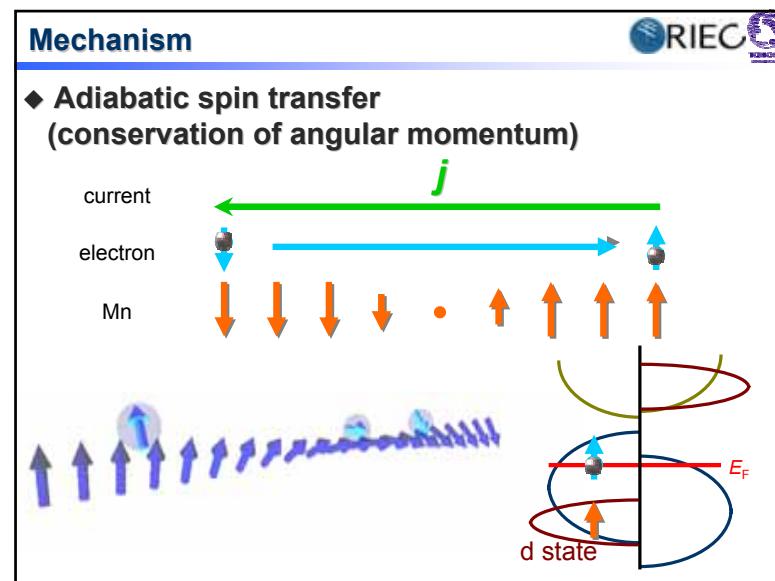
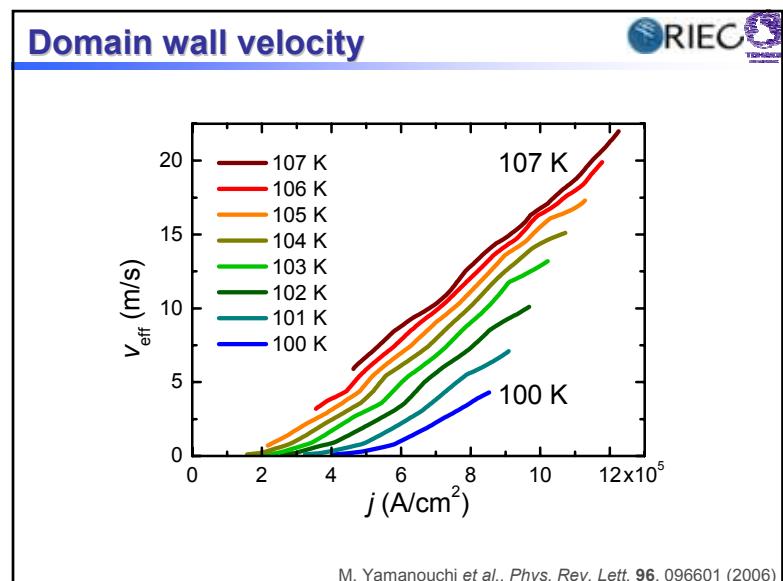
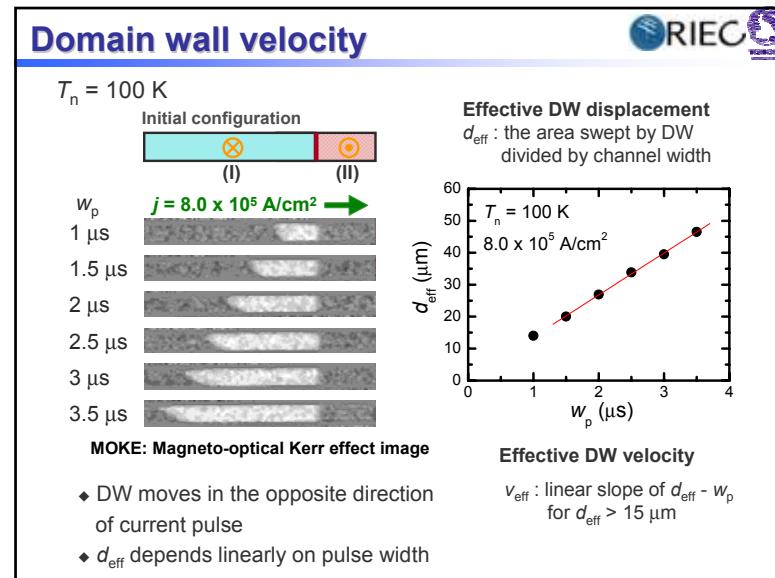
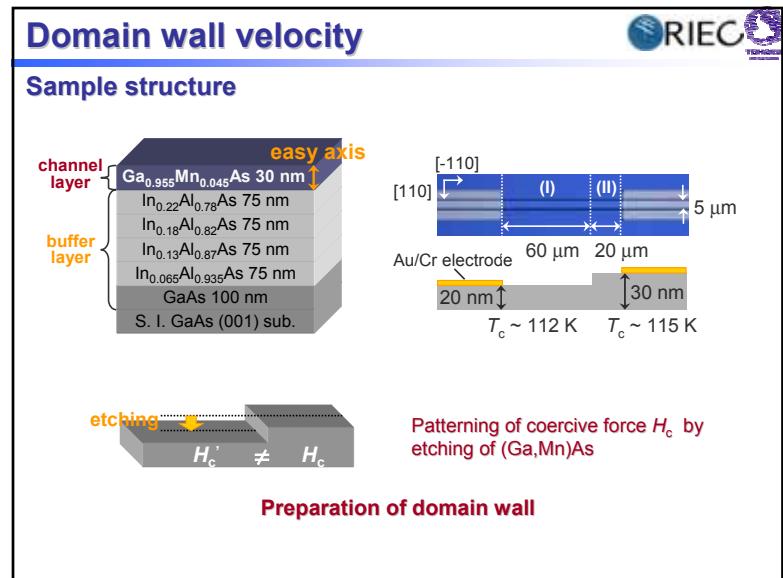




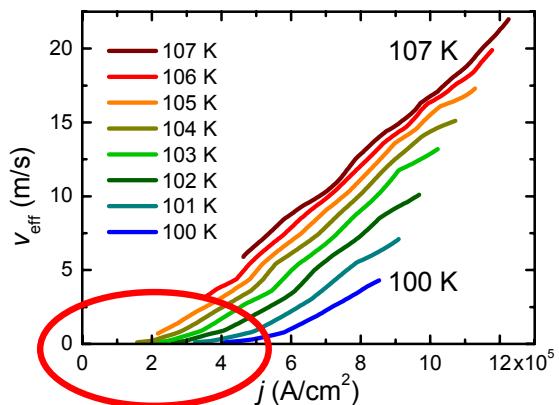


1. Ferromagnetic III-V semiconductors
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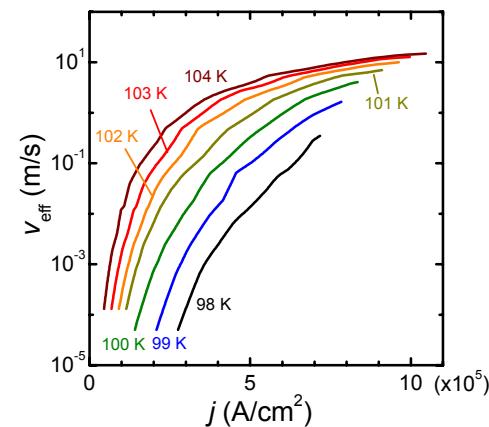


Domain wall velocity



M. Yamanouchi et al., Phys. Rev. Lett. **96**, 096601 (2006)

Velocity: Sub-threshold regime



Current assisted domain wall creep

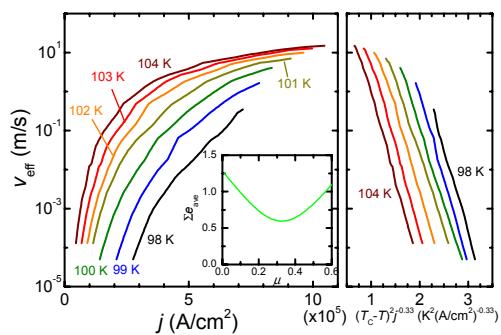


$$\ln(v(H)) = v'_0 - \frac{U_{cw}}{k_B T} \left(\frac{H_{\text{crit}}}{H} \right)^{\mu}$$

Lemerle et al. PRL **80**, 894 (1998)

$$\ln(v_{\text{eff}}) = a - b j^{-\mu}$$

$\mu = 0.33$



DW motion by magnetic field

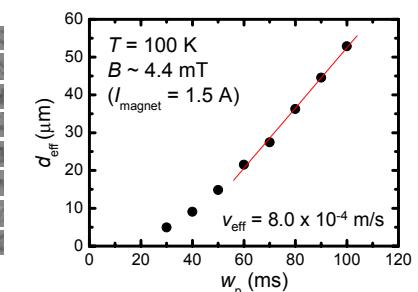
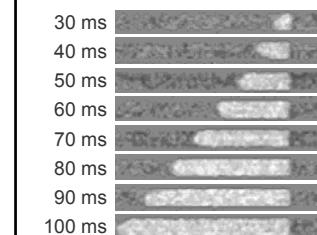


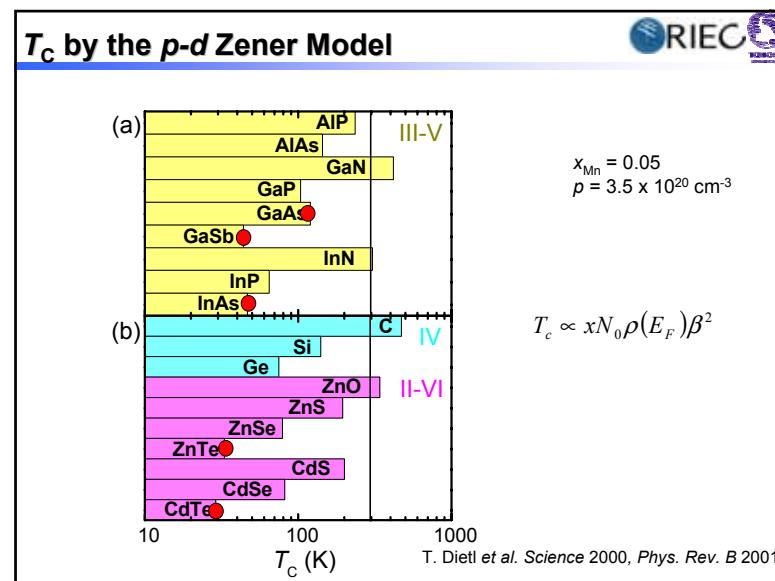
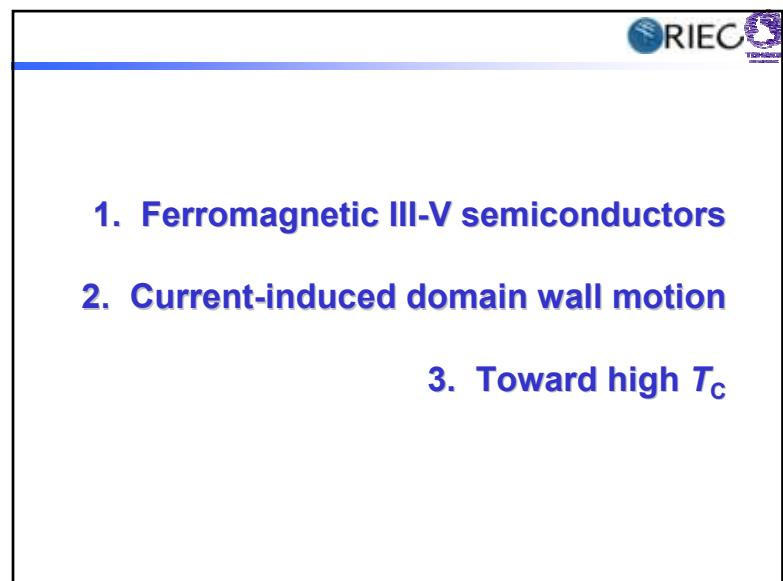
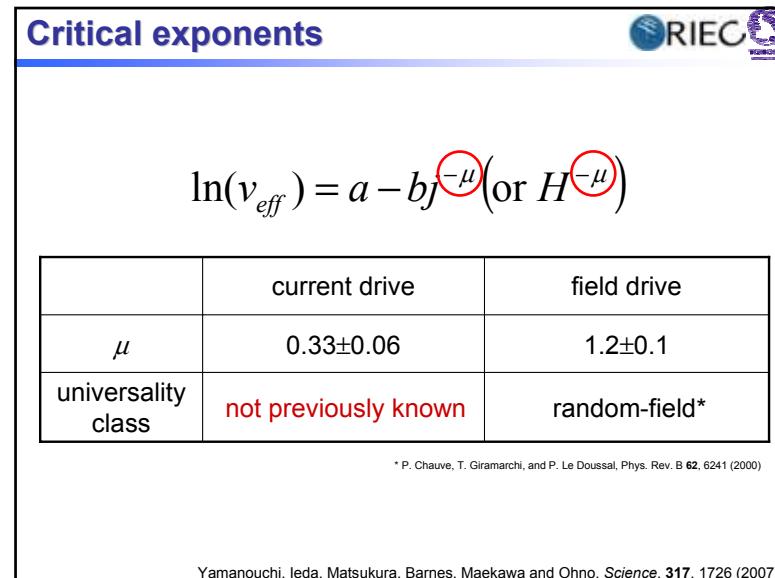
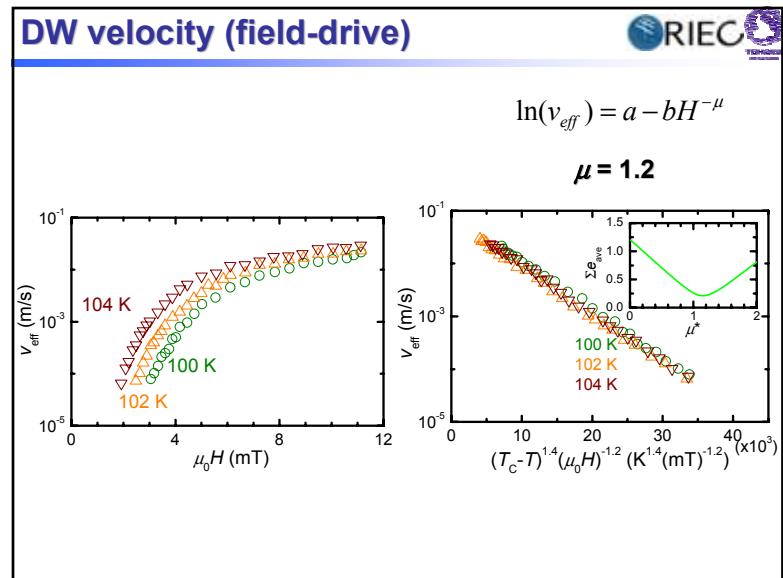
100 K

Initial configuration



width $\odot B \sim 4.4 \text{ mT}$





(Al,Cr)N and Ge:Mn

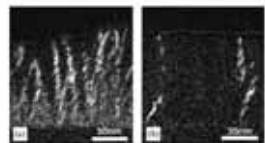


Fig. 1. Energy-dispersive electron microscopy showing Cr precipitates in Al_{0.75}Cr_{0.25}N film, annealed at 700 °C, and Cr-doped AlN; Mn 2.5% Cr-doped AlN.

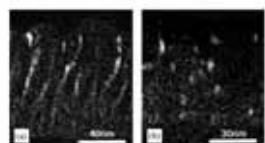


Fig. 2. Energy-dispersive electron micrographs showing Cr distribution in 4% Cr-doped AlN grown at different annealing temperatures: (a) 700 °C; (b) 800 °C.

L. Gu *et al.*, JMMM, 290-291, 1395 (2005)

M. Jamet *et al.*, Nature Mat., 5, 653 (2006)

Four different cases



Metallic random alloy

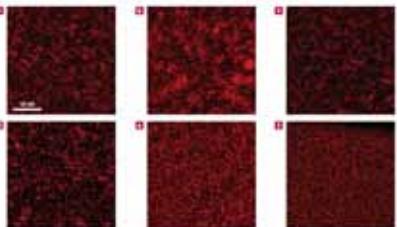
Electronic phase separation

Chemical phase separation on the same lattice

- can stabilize a structure that does not exist in its bulk form
- a new route to nanostructure formation

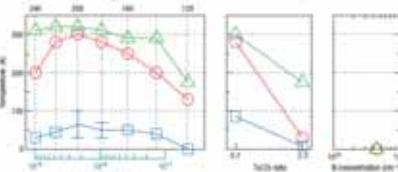
Precipitates with different crystal structures

The case of Zn_{0.94}Cr_{0.06}Te

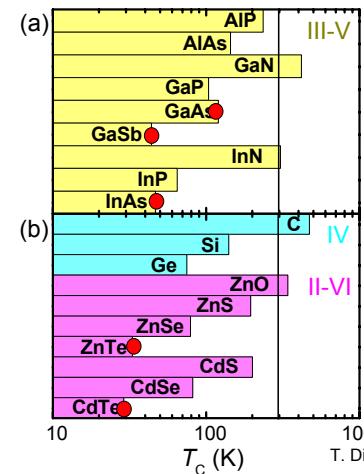


S. Kuroda *et al.*, Nature Materials 2007
(Univ. Tsukuba)

Figure 3. Distributions of Cr distribution in a sample of (Zn_{0.94})_{0.94}Cr_{0.06}Te. Cross-sectional microscopy images (EDS mapping) for a sample of (Zn_{0.94})_{0.94}Cr_{0.06}Te with Mn concentration = 0.05 mol% and difference in Cr-doping concentration = 0.01 mol%. As a result, Mn atoms are concentrated at the grain boundary.



T_C by the p-d Zener Model



$$x_{\text{Mn}} = 0.05$$

$$p = 3.5 \times 10^{20} \text{ cm}^{-3}$$

$$T_c \propto x\rho(E_F)\beta^2$$

T. Dietl *et al.*, Science 2000, Phys. Rev. B 2001

